Neural Network Control of Chemical Mechanical Planarization

ABSTRACT OF THE DISCLOSURE

Broadly speaking, a method for controlling a chemical mechanical planarization
(CMP) process to obtain a desired result is provided. More specifically, the method
incorporates a first neural network to estimate a CMP result and a second neural network
to tune CMP control parameters used to obtain the CMP result. The second neural network
tunes the CMP control parameters to minimize a difference between the CMP result and a
desired CMP result.